

Insights: Publications

Replacing C-V Monitoring with Non-Contact COS Charge Analysis

Yield Management Solutions

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Monitoring contamination levels in diffusion furnaces is necessary to ensure that a consistent environment is maintained for the protection of semiconductor devices. Due to the large load sizes of diffusion furnaces, there is a potential for significant amounts of scrap if adequate contamination monitoring is not maintained. In addition, a significant amount of product remains at-risk if contamination monitoring is not performed in a timely manner. Clearly, the value of monitor data is greatest immediately after a product run and this value decreases with time.

Related People



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